



**adolphe merkle institute**  
excellence in pure and applied nanoscience

UNIVERSITY  
OF FRIBOURG  
SWITZERLAND

## Focused ion beam

### Introduction

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TOMOGRAPHY – SLICE AND VIEW





## ***Universal rules***

**Rule 1: don't touch a control if you are not sure of the outcome of that action**

**Rule 2: never, ever force anything beyond finger strength**

**Rule 3: wear gloves when touching anything that goes into the chamber**

**Rule 4: if in doubt, ask for help**

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## Demonstration: Starting up Auto Slice and view

### Prerequisites:

Running xT server

Running UI

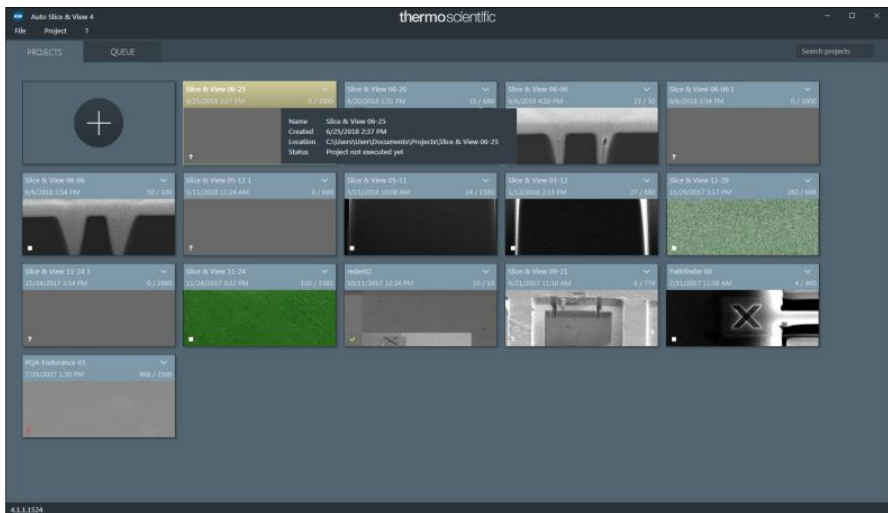
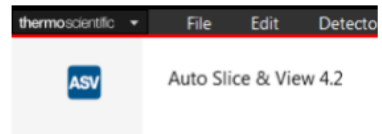
### Action:

Slice and View software

## Load the dedicated tomography software

To launch the application:

- Double-click the ASV icon on the Windows desktop,
- Or select the Thermo Scientific toolbar button / Auto Slice & View



The software opens. Place the window on the rightmost screen

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- Starting a new project

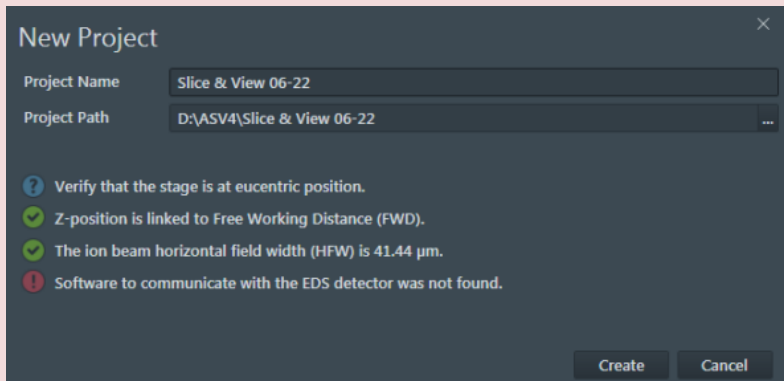
---

## Prerequisites:

- At Eucentric height
- Z is Linked
- HFW between 10 – 150  $\mu\text{m}$

**Experiment: starting a new project**

1. Load a sample onto the stage
2. Navigate to the feature of interest and place it in the center of the field of view.
3. Set the sample to the eucentric position.
4. Tilt the stage to 52°.
5. Ensure that the electron and ion beams are coincident.
6. Verify that the image shift, when changing ion column aperture is minimized.
7. Optimize electron beam focus.
8. Run the Link Z to FWD procedure.
9. Set the ion beam horizontal field width within the range 10 – 150  $\mu\text{m}$ .
10. Select the Stage menu / Enable Safe Stage Moves item on the microscope UI
11. In the slice and view software, click the big + to start the new project effect.



- Enter an unique project name.
- Save on a folder in the SharedData drive. NOT on the local drive.



## Demonstration: The milling page

### Prerequisites:

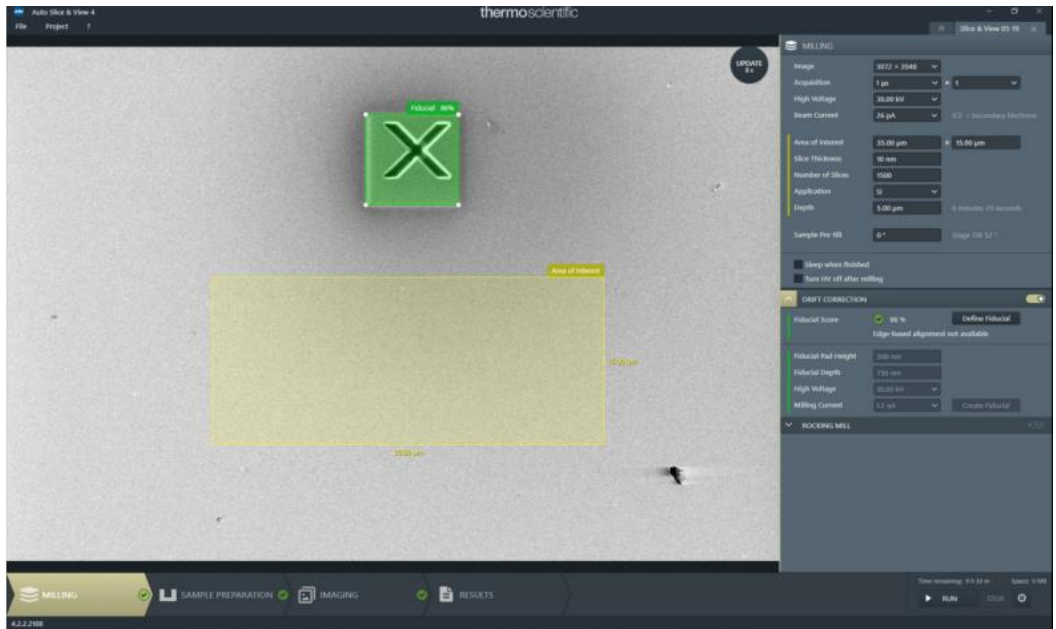
Area of interest located, 52°

xT location focused and stigmated

### Background on the ion beam

Set up the milling controls and the drift correction / fiducial parameters.

In the **ion image**, the slicing/milling area is indicated by a yellow rectangle. The fiducial point area is indicated by a red rectangle; when the fiducial point is defined, this area changes to green.



### Controls

## **Image**

The resolution of the image to be used to grab the drift correction images. It is described by the pixel count in an image as: number of pixel columns × number of pixel rows. The higher the resolution, the more image detail can be seen. Consider selecting a higher resolution if milling < 20 nm slice thickness.

## **Acquisition**

The dwell time to be used to acquire the images and the number of frame integration.

## **High Voltage**

The ion beam accelerating voltage. Always 30 kV!

## **Beam Current**

The ion beam current to be used for milling (and imaging!). Select a current high enough to mill the sample in a reasonable time, but low enough to guard against sample damage and loss of image resolution. Estimated milling time for one slice is indicated at the bottom right of the module. Rule of thumb is that milling time + imaging time should be about 1 minute. Typically, currents between 0.5 and 5 nA are used.

## **Area of Interest** (width × height)

The width and height of the slicing area as defined by the yellow rectangle. Changing the height will adapt the number of slices to height/slice thickness.

## **Slice Thickness**

The targeted thickness of each slice. Changing this value will adapt the number of slices to match the new thickness.

## **Number of Slices**

The number of slices to be made in the automated slicing phase. Changing this value will adapt the height of the milling site to match slice thickness and number slices.

## **Application**

A GIS material application that is appropriate for the sample under investigation. Typical Pt Deposition.

## **Depth**

The relative depth of the slicing area, depending on the kind of sample, sample geometry, etc. The depth is set by application, but it can be changed by typing a value, typically between 0.5 and 100 μm

## **Sleep when finished**

Force the system to sleep after the project has been finished.

**Turn HV off after milling**

Only used with rocking mill. It switches of the ion beam accelerating voltage

during a long lasting electron beam imaging (when the screen resolution and dwell time are set high).

**Note Y-shift correction and compensation for the change in the Working Distance in the SEM images through the slicing job will fail, if a sample Pre-tilt is not set up correctly**

- 
- Drift correction module
- 

FIB drift correction is needed for accurate processing results: a higher slice thickness accuracy and placement of individual slices can be achieved. It refers to the placement of the pattern for milling, not image drift.

A fiducial point is used for FIB drift correction during the entire slicing process.

**Position**

The position of the fiducial point has to be some distance apart from the milling, but also within the imaging area borders. Ideally, it is placed right or left of the region of interest.

**Fiducial Pad Height**

The deposited height of the protective Pt layer, wherein the fiducial point will be milled. Defaults are rather low.

**Fiducial Depth**

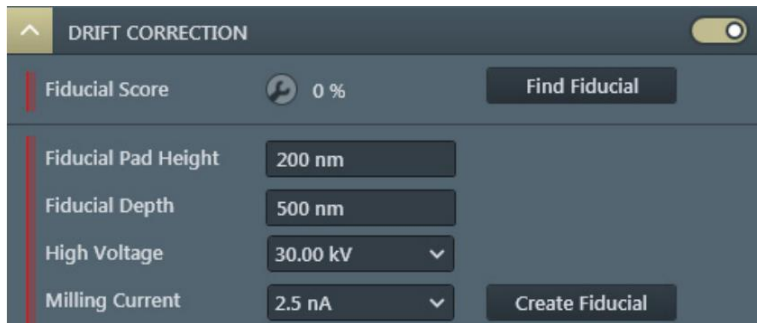
the depth of the cross patterns.

**High Voltage**

The ion beam voltage used to mill the cross patterns; ie. 30 kV

**Milling Current**

The application should suggest a suitable milling current according to the fiducial rectangle size



### Experiment: Creating a fiducial marker

1. In the microscope UI, optimize the ion beam imaging parameters using the current you have set in the AS&V beam current settings (usually 0.5-5 nA). Adjust stage position and magnification so the region of interest is centered and sufficient space around is available for a fiducial marker.
2. In the AS&V, click Create fiducial.

After completion, the fiducial marker will be searched for and if successfully found, the software will proceed to the Sample Preparation page.

If the fiducial marker could not be found: optimize the fiducial point image by using the microscope UI and use the find the fiducial manually.

### Manually finding fiducial point

If the marker could not be found automatically, try a slightly more manual approach.

### Experiment: Manually finding a fiducial marker

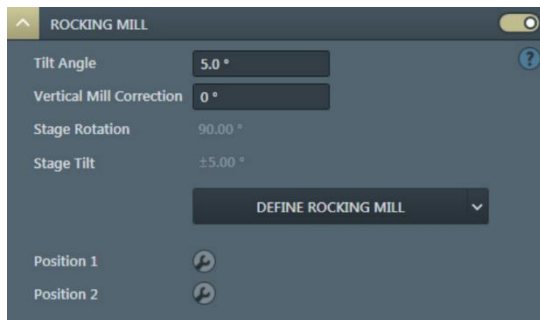
1. In xT UI, optimize the ion beam imaging parameters using the current you have set in the AS&V beam current settings (usually 0.5-5 nA). If needed, increase the scan time.
2. In the AS&V UI, click the update button to refresh the ion beam image.
4. manually resize and reposition the yellow box to cover the cut face area of interest.

5. Then click the Find Fiducial button. A new image will be grabbed to determine the Fiducial Score (in %) of the selected fiducial point. The higher the score, the better the fiducial point.

If the fiducial point is found, the software stores acquisition settings to use when locating the fiducial point during the automated run. From now on the fiducial point is locked in, the yellow box can be resized but cannot be moved.

- 
- Rocking mill (optional)
- 

Vertical direction milling is a common practice used by FIB for milling series of 2D slices. It achieves milling in two different directions alternatively (under/overtilt) with a defined angle away from either side of the vertical milling direction to suppress a curtain effect.



## Demonstration: Sample preparation

### Prerequisites:

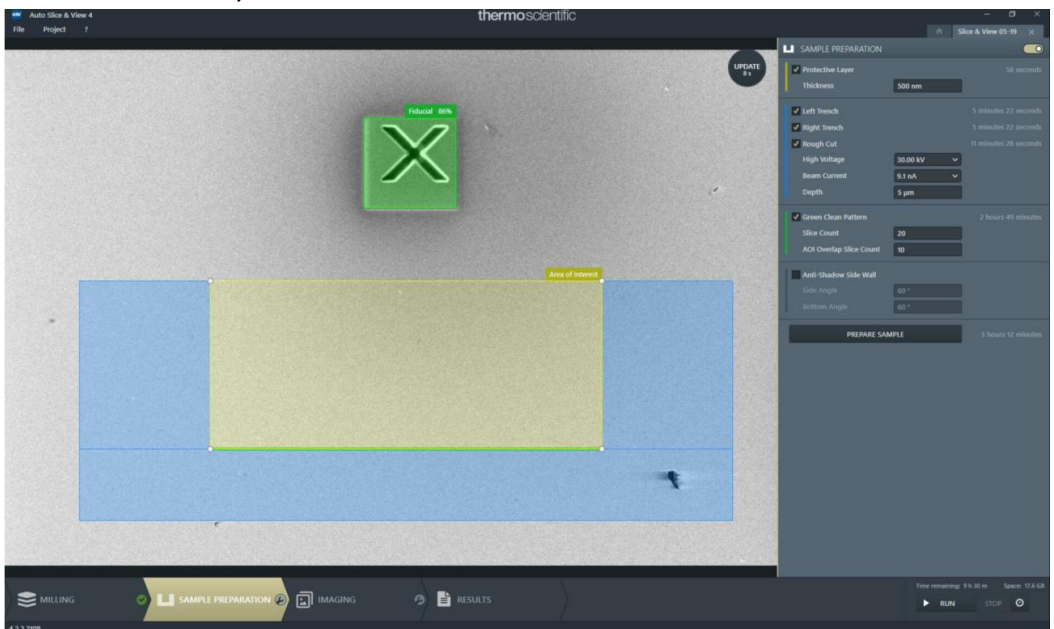
- Fiducial marker placed and found
- Area of interest defined

### Learn to switch e-beam and ion beam on

Ticking the check box(es) enables the option(s), corresponding areas within the image are colored in the same way as in the module.

The time value on the right side next to the corresponding items shows the estimated milling time. The Beam current and milling area dimensions are the main factors which influence the time.

The blue rough cut and trench cut areas, just as the yellow area of interest (or Protective layer area) can be modified graphically by dragging and dropping the selection boxes on the corners and sides of each rectangle. The Left Trench and Right Trench can not be used simultaneously with the Anti-Shadow Side Wall.



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- Protective Layer

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selecting this option deposits a protective Pt coating over the intended milling area. Typically, this is done manually before.

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- Left / Right Trench

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The trench cuts provide a place for material to be deposited as slices are milled away from the area of interest during the automated run. They are represented as blue rectangles to the right and left of the yellow milling area rectangle. Mills standard cross sections to produce the rough cut and trench cuts.

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- Rough Cut

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The rough cut exposes the front face (= the cross section) of the feature of interest for electron beam imaging. Its size and location are represented as a blue rectangle on the ion image.

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- Green clean pattern

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A Green Clean Pattern (GCP) is an optional polishing step of the sample cut-face for immediate data acquisition by milling away a user-defined number of slices at low voltage and current. The depth is the same as the standard slice depth (as set in the milling page). The GCP area is represented by a green box in the image area.

- The milling occurs at the voltage, current, and depth specified on the Milling page.
- The width of the green box is restricted to be the same width as the yellow area of interest (AOI) box.
- The height of the green box is unrestricted, but typically it will be very small (10-20 slices). It represents a Slice Count – number of slices (text box), that will be milled.

- The AOI Overlap Slice Count text area specifies the number of GCP slices, that overlap the bottom of the area of interest.<sup>1</sup> If you stop the milling within the area of interest, the software will know where to begin during the automated slicing process.

- 
- High Voltage / Beam Current
- 

The ion beam voltage / current to use when milling the Trench cuts, Rough cut, and Anti-Shadow Side Wall. (note: the voltage and Beam current of the green clean pattern are set on the milling page)

- 
- Depth
- 

The depth of the selected milling pattern area

- 
- Anti-Shadow Side Wall
- 

Mills an anti-shadow angles for EBSD processing.

### Experiment

Click the Prepare Sample button to start the milling of all selected options.

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<sup>1</sup> If you are watching the milling process on the microscope UI and you decide that enough of the GCP has been milled, you can stop the milling at the end of the actual slice by clicking the Abort button.



## Demonstration: Imaging

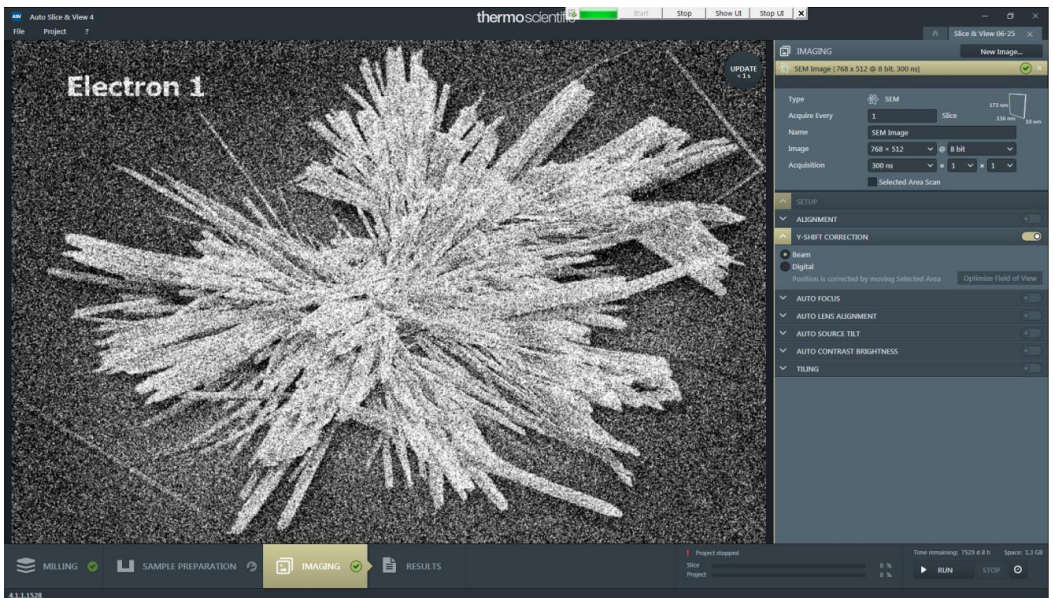
### Prerequisites:

At least trenches and rough cut milled.

### Start the procedure of slice and view

Before proceeding with the items on the Imaging page, make sure the site is prepared for imaging. In the xT UI:

1. check and if needed adjust the microscopy conditions such as accelerating voltage, beam current, and detectors for each display.
2. Optimize the imaging parameters such as lens alignment, focus, astigmatism correction, and brightness & contrast.

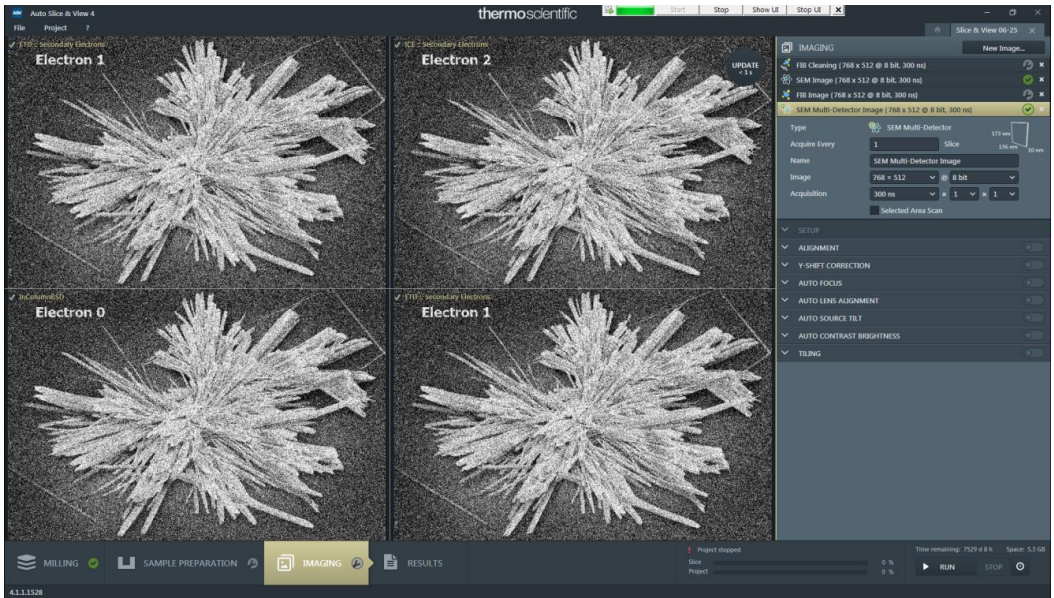


- Imaging controls

## Acquisition types

There are several possible types of acquisition selectable from the drop-down menu when clicking the New Image... button. By selecting any item, a new line (an image series, that will be taken every slice) is added to the list, with the corresponding settings.

For the xT UI detectors (ETD, T1, T2,...), select the SEM Multi-Detector:



This allows to select the quadrant that contain meaningful detectors.

Assuming the detectors are set up in the microscope UI, select the desired display(s) to include by checking its check box at the top-left corner. All selected displays must have the same beam (e-beam). By clicking the update button, the settings are updated and the image(s) is/are acquired in it's associated display.

- Detector setup

## Type

The beam used by this acquisition type.

## Voxel cube

The size dimensions are dependent on the resolution, HFW, slice thickness, stage position and tilt correction settings. A tooltip gives a hint about setting of the isometric (cubic) voxel.

## Acquire Every # Slice

The interval between slices to be acquired. You can e.g. only record every  $n^{\text{th}}$  slice.

## Name

A meaningful name for the actual image series.

## Image

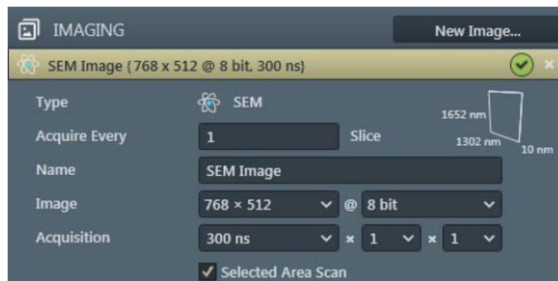
The image resolution and its bit depth (always 16 bit!)

## Acquisition

the dwell time, number of lines integration and number of frames integration to be used for this image series.

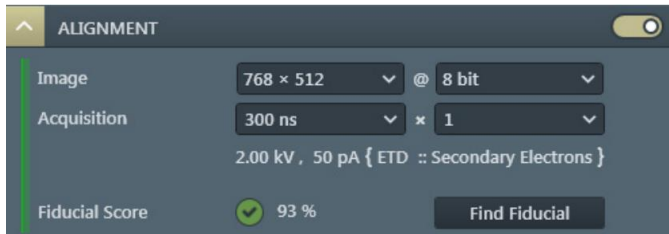
## Selected Area Scanning

if checked, only selected area will be scanned for imaging (see below)



- The alignment module

An automatic image stack alignment. It is used to get all of the images aligned with one another. The user specifies a unique feature to look for (tip: use the fiducial point) and then for each slice it beam shifts the image so that the fiducial point always appears in the same spot.



### Image

The image resolution and its bit depth (16 bit!).

### Acquisition

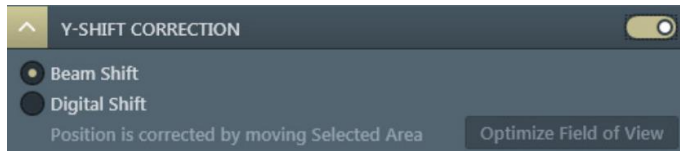
the dwell time, number of frames to be integrated for the images used to align the final cut face area during the automated run.

### Find Fiducial

Clicking this button positions the sample, performs auto-contrast and brightness if activated, and finds the fiducial marker. Alignment configuration is not complete until you click this button.

- Y-shift correction

In perpendicular SEM imaging, the sample is tilted in such a way, that the plane of the cut face is perpendicular to the electron beam, that results in the most accurate image. Normally an electron beam imaging is under  $52^\circ$ , so each slice causes a little image shift. To compensate this behavior for every slice, activate this module and select a desired method by checking the radio button.



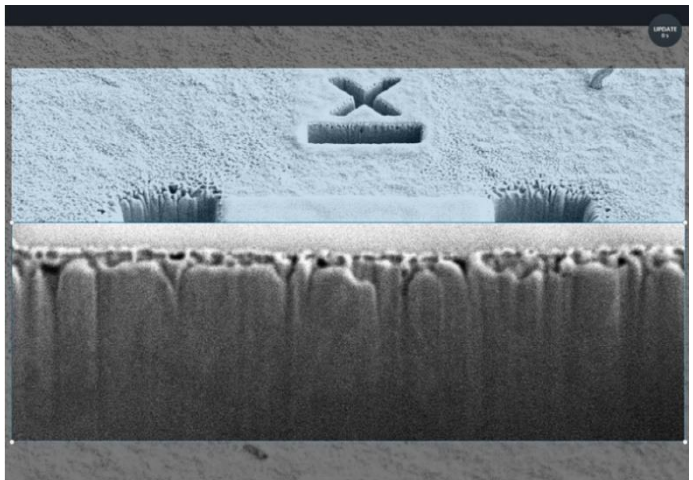
### Beam Shift

compensates an image shift by changing the beam focus. There is limited beam shift to make use of, and the detector mode also affects available beam shift.

### Digital Shift

starts the Selected Area Scan for a corresponding image series, and compensates an image shift by shifting of this area. Below: the lower (clear) area is the actual selected area, the area above (bluish) delineates, where the digital shift will take place.

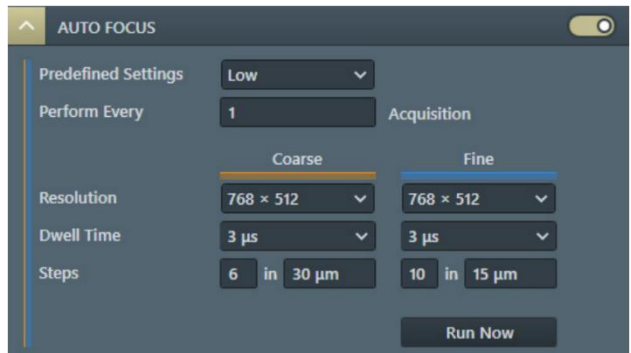
Dimensions of these areas are set by an application, they are influenced by AOI dimensions. The image above shows the situation after clicking the Optimize Field of View button, causing extension of the AOI to fill the display optimally.



- Auto focus module

The auto focus functionality is performed before every  $n^{\text{th}}$  acquisition of a series. An orange area with a blue border is positioned over the image to visualize the autofocus FOV. Position and size of the reduced area can be adjusted. The autofocus is based on “sweeping”

the working distance in a two-step approach over a specified range while measuring image sharpness. First a Coarse sweep (orange color) to get close to focus is performed, followed by a Fine sweep (blue color) to optimize it. Tune the parameters – the autofocus needs a good quality image - and run the auto focus prior to starting a project execution.



**Place the autofocus window on a horizontal axis – same working distance – as your cut face (e.g. the fiducial marker).**

### Predefined Settings

(Low / Medium / High / Custom) are different preset settings to the multiple controls.

### Perform Every # Acquisition

Specifies how often the autofocus should be performed.

### Resolution

The pixel resolution of images acquired during the focus sweep.

### Dwell Time

The amount of time the beam dwells on each pixel when images are acquired during the focus sweep. The higher, the less noisy the images are and the higher the chance for a good autofocus.

### Steps

The number of working distance (WD) steps in which the range will be sampled:  $\text{WD step size} = \text{range} / \text{steps}$ .



**Perform Sweep or run now button**

performs an auto focus sweep with the configured settings and shows image

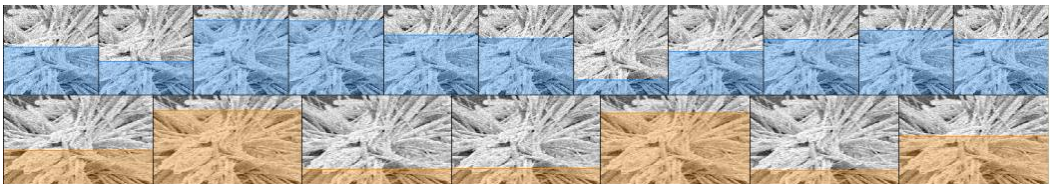
series of both sweeps distinguished by the color.

**Best Practices**

There is always a trade-off between accuracy, speed, robustness, and sample exposure. The auto focus functionality is designed to work well even when the images appear “noisy” to the human eye. (low dwell times, low resolutions, high magnifications).

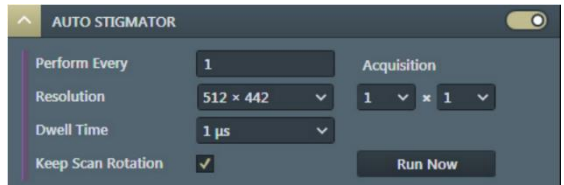
<u>Time</u>	is mainly determined by acquisition speed and number of steps.
<u>Position</u>	place your marker on line with your FOV, not in front or behind
<u>Resolution</u>	lower resolution and smaller dwell times will increase acquisition speed at the slight cost of accuracy and robustness.
<u>Step number</u>	higher number of steps increases the accuracy, but comes at the price of speed. Note that the coarse / fine sweep helps out here.
<u>Range</u>	rule of thumb: the range of the fine sweep should be a few times the step size (i.e., range divided by steps) of the coarse sweep.

The colored images obtained during the autofocus run indicate the success of the auto focus. The higher the colored bar, the better the focus. The application selects automatically the best result (i.e. the highest bar). Ideally, both the orange and blue indicator follows a rough gaussian curve.



- Auto stigmator

The auto stigmator functionality is performed before every  $n^{\text{th}}$  acquisition of the series. A squared reduced area is positioned over the image to visualize the auto stigmator FOV (can be the same as the autofocus FOV).



### Best Practices

- Location The auto stigmator functionality slightly adjusts the working distance, therefore: place the reduced area FOV at a location having the same working distance as the cut face (see also remark autofocus).
- Marker The reduced area FOV should contain structures in various directions to ensure a good correction of astigmatism. Areas without any texture or areas with 1-directional patterns such as lines are not recommended. The fiducial cross is usually a good choice.
- Size The area must have an area at least 100×100 pixels.
- Scan Rotation Untick this box to simulate the behavior of Auto Stigmator functionality in the UI (uses rotation), that changes scan rotation value.

Clicking the Run Now button starts the functionality immediately.

- Auto lens alignment

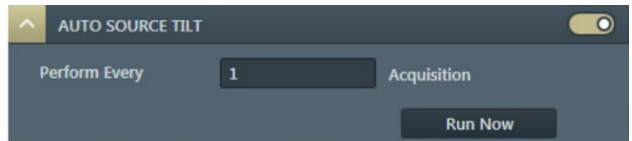
The auto lens alignment functionality is performed before every  $n^{\text{th}}$  acquisition of a series. A squared reduced area is laid over the image to visualize which part of the field of view will be used.





- Auto source tilt

When activated, the auto source tilt functionality is performed before every  $n^{\text{th}}$  acquisition of this series.



- Auto contrast brightness

When enabled, applies ACB (Auto Contrast Brightness) to each image acquisition set in the Perform Every  $n^{\text{th}}$  Acquisition. It determines whether or not an ACB is done before acquiring the image during the automated run. A reduced area is positioned over the image to visualize which part of the field of view will be used. Here, it is advised to use a part on the side of your cut face and not the fiducial marker, as the B/C signal of the marker (Pt) may not reflect the B/C signal of your object.

- Tiling

When activated, a set of tiles of the cut face area is grabbed instead of a single image.



### Columns / Rows

the number of columns and rows of the grid used for tiling. An image / map will be acquired for each tile.

### Tile Overlap

defines the percentage of each tile that will be overlapped during image acquisition to provide a reference area

in the images for reconstructing a composite image of all tiles.

### Final Image Resolution (info field)

Shows the microscope UI settings of the image resolution.

### Enable Stitching

when ticked, this service stitches the image tiles to produce one large image.

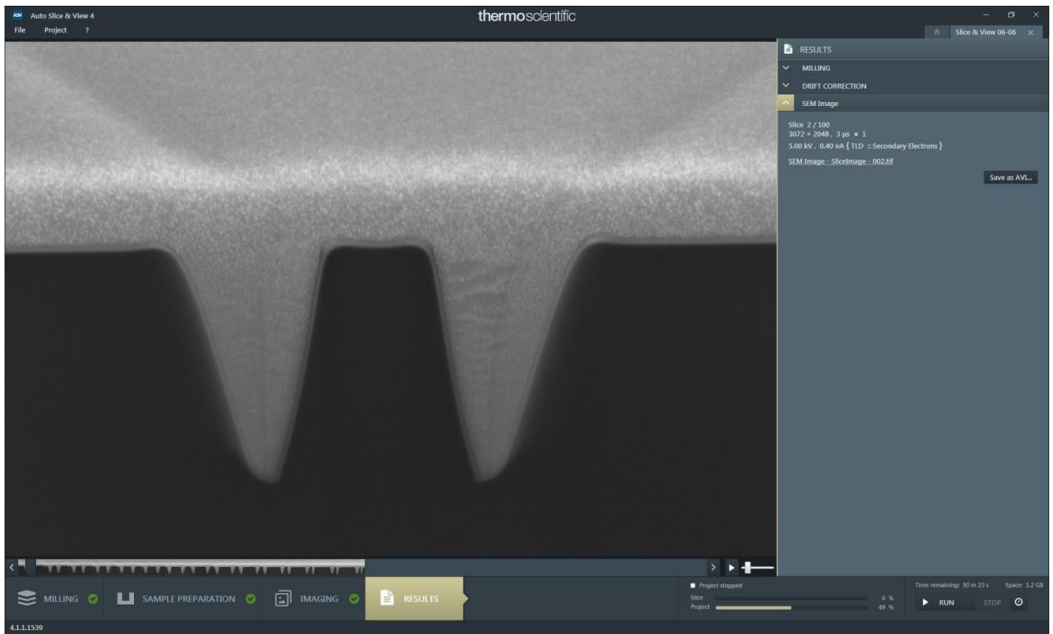
**Note: Tiling can only be enabled for SEM images and is recommended only for imaging with the electron beam perpendicular to the cut face.**

**Demonstration: Results****Prerequisites:**

Tomography running or finished

**Collect your recorded data**

This page is the same for viewing the results (images) as they come in during processing as well as for viewing a previously executed project. The modules on the right side of the page shows each resulting image series (as defined in the imaging page). The imaging area shows any image from the series by moving the slider at the bottom.



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- Image series modules

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The controls / information within these modules have the same meaning:

**Slice:** gives the serial number of shown image / number of all images

**Image:** Image resolution, dwell time, number of frames integration for this image

**Microscope:** Accelerating voltage, beam current, {detector type and its mode}

**Result:** Active item with the image series name – clicking it redirects you to the corresponding images folder.

**Save as AVI...:** clicking this button enables the creation of an AVI type movie from the image stack. A File dialog appears to specify a file name and select a directory for the resulting AVI file. •

**AF / ACB:** informs, that the auto focus / auto contrast brightness image processing is in progress for the actual slice.

**Export to CSV...:** used to export the drift correction data to the format readable by most table processor applications.



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